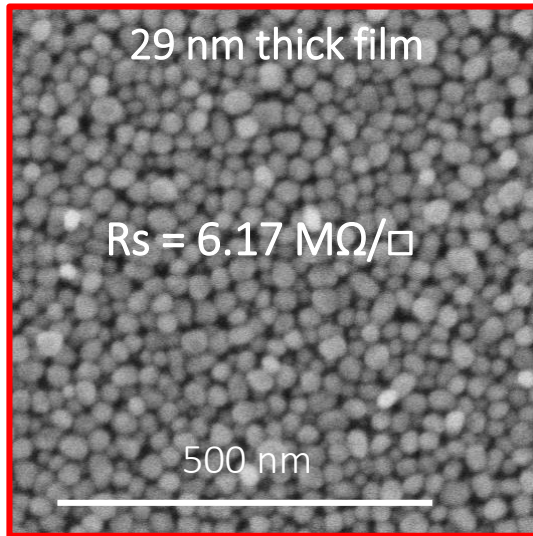


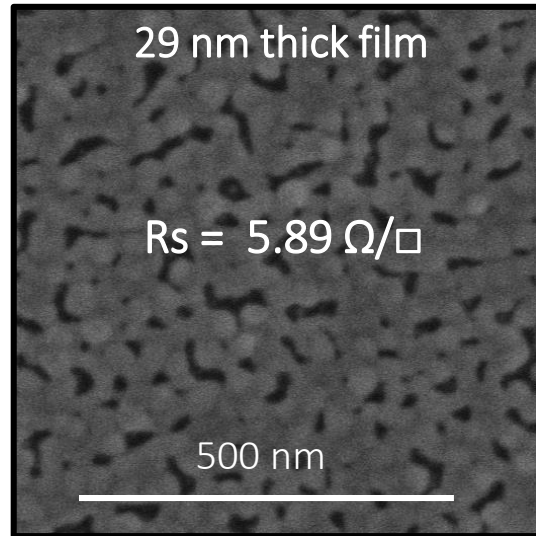
## Product 1

Plasma-enhanced  
deposition

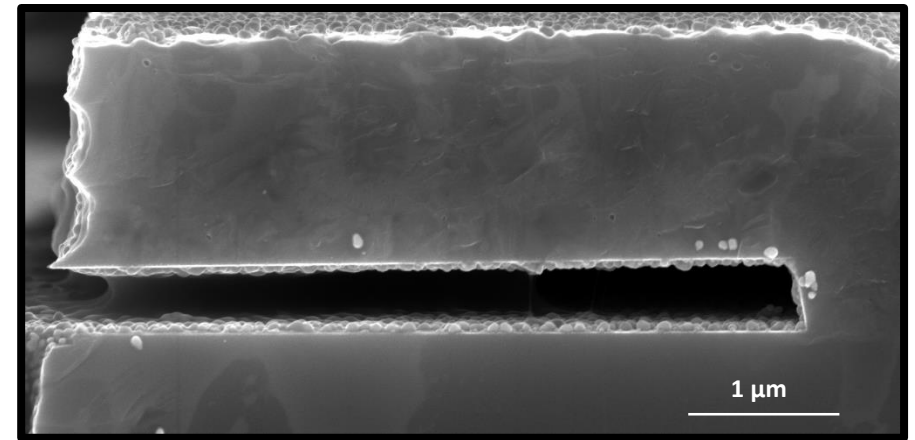


## Product 2

After  
post-treatment



Scanning Electron Micrographs (top view) of Ag thin films (29 nm thick) deposited on glass substrates showing the principle of the two-step processing : product 1 obtained by plasma-enhanced deposition exhibiting a high sheet resistance  $R_s$  (left) and product 2 obtained after post-treatment exhibiting a low sheet resistance  $R_s$  (right). The scale bars represent 500 nm.



Scanning Electron Micrograph (cross section) of Ag thin film deposited on lateral high aspect ratio structure (10:1) showing the degree of conformality of the film. The scale bar represents 1  $\mu\text{m}$ .